L Number	Hits	Search T xt	DB	Time stamp
1	5	(p lysilicon adj tra) and lin r and oxid	USPAT;	2004/07/07
		and sid wall and spacer and (silic n adj	US-P PUB;	14:36
		nitride) and (L near (shape r shap d or	EPO; JPO;	
		shaping))	DERWENT;	
			IBM_TDB	
2	5	((conductive or conducting or polysilicon)	USPAT;	2004/07/07
		adj trace) and liner and oxide and sidewall	US-PGPUB;	14:38
		and spacer and (silicon adj nitride) and (L	EPO; JPO;	
		near (shape or shaped or shaping))	DERWENT;	
			IBM_TDB	
3	16	(gate near3 polysilicon) and (source or	USPAT;	2004/07/07
		drain or source/drain) and liner and spacer	US-PGPUB;	14:44
		and (silicon adj nitride) and (I near5 spacer)	EPO; JPO;	1-33-3-3
		and (sincental) intride; and (i neare spacer)	DERWENT;	
			IBM_TDB	
4	.0	(gate near10 (source or drain or	USPAT;	2004/07/07
		source/drain) near10 liner near10 oxide	US-PGPUB;	14:45
		near10 (silicon adj nitride) near10 spacer	EPO; JPO;	17.70
		near10 (I near (shape or shaped))).clm.	DERWENT;	
		near to trinear (snape or snapeu)), cinn	IBM_TDB	
6	0	(gate near10 (source or drain or	USPAT;	2004/07/07
	U	source/drain) near10 liner near10 oxide	US-PGPUB;	14:45
		near10 (silicon adj nitride) near10 spacer	EPO; JPO;	14:43
		near 10 (sincon auj intride) hear 10 spacer near10 (I near (shape or shaped)))	DERWENT;	
		near to (i near (snape or snaped)))	IBM_TDB	
	0	(gate near10 (source or drain or	USPAT;	2004/07/07
	•	source/drain) near10 liner near10	US-PGPUB;	14:45
		(insulating or dielectric or oxide) near10	EPO; JPO;	14:45
		(silicon adj nitride) near10 spacer near10 (l	DERWENT;	
		near (shape or shaped)))	IBM_TDB	
	3	(gate same (source or drain or source/drain)	USPAT;	2004/07/07
	3	, ,	US-PGPUB;	14:48
		same liner same (insulating or dielectric or	· ·	14:40
		oxide) same (silicon adj nitride) same	EPO; JPO;	
		spacer same (I near (shape or shaped)))	DERWENT;	
8	7	(I near? (changes as change) near?	IBM_TDB	2004/07/07
	•	(I near2 (shape or shaped) near3	USPAT;	2004/07/07
		spacer).clm. and liner.clm. and	US-PGPUB;	14:59
		polysilicon.clm. and gate.clm. and (source	EPO; JPO;	
		or drain or source/drain).clm.	DERWENT;	
	24	(manua (nhana an ahaira 4)a)	IBM_TDB	2004/07/07
9	21	(I near2 (shape or shaped) near3 spacer)	USPAT;	2004/07/07
		and liner and polysilicon and gate and	US-PGPUB;	15:00
		(source or drain or source/drain)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	